



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Robert Bristol et al. § Group Art Unit:
§
§
§ Examiner:
§
§
For: Enhancing Photoresist Performance § Atty. Dkt. No.: ITL.1023US (P16710)
Using Electric Fields §

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicant submits the references listed on the attached form PTO 1449 together with any required copies of such references.

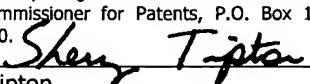
This statement is being filed within three months of the filing date of the application.

Please apply any charges or credits to Deposit Account No. 20-1504 (ITL.1023US).

Respectfully submitted,

Date: 
2/30/03


Timothy N. Trop, Registration No. 28,994
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Date of Deposit: December 30, 2003
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Sherry Tipton

<p style="text-align: right;">O I P</p> INFORMATION DISCLOSURE CITATION <small>(Use several sheets if necessary)</small> <small>JAN 02 2004</small>				ATTY DOCKET NO. ITL.1023US (P16710)		SERIAL NO. 10/679,816	
				APPLICANT(S): ROBERT BRISTOL ET AL.		FILING DATE: October 6, 2003	
U.S. PATENT DOCUMENTS							
PATENT & TRADEMARK OFFICE INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
A.	5,158,861	10/27/1992	TOKUI ET AL.	430	325		
B.							
C.							
D.							
E.							
F.							
G.							
H.							
I.							
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO	
J.							
K.							
L.							
M.							
N.							
O.							
P.							
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
Q.	Cheng et al., "Improving Resist Resolution and Sensitivity Via Electric-Field Enhanced Postexposure Baking", J. Vac. Sci. Technol. B 20(2), Mar/Apr 2002						
R.							
S.							
T.							
U.							
V.							
W.							
EXAMINER				DATE CONSIDERED			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							